IEEE SW Test Workshop Semiconductor Wafer Test Workshop

June 12 to 15, 2011 San Diego, CA



Kevin Fredriksen / MSO – Multi Site Optimizer For IEEE SW Test Workshop



Kevin Fredriksen, SPA GmbH Germany Customer support / Sales

OVERVIEW

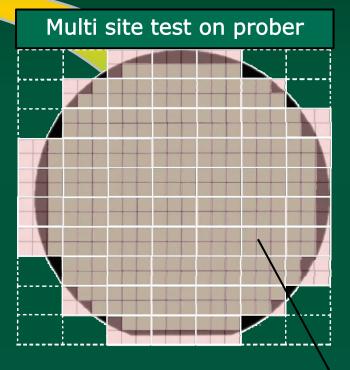
- MSO HISTORY
- MSO basics and facts
- Optimization example
- Multi site layouts & touchdown options
- Stepping path algorithms
- MEMS wafer test a multi site quest!
- Summary







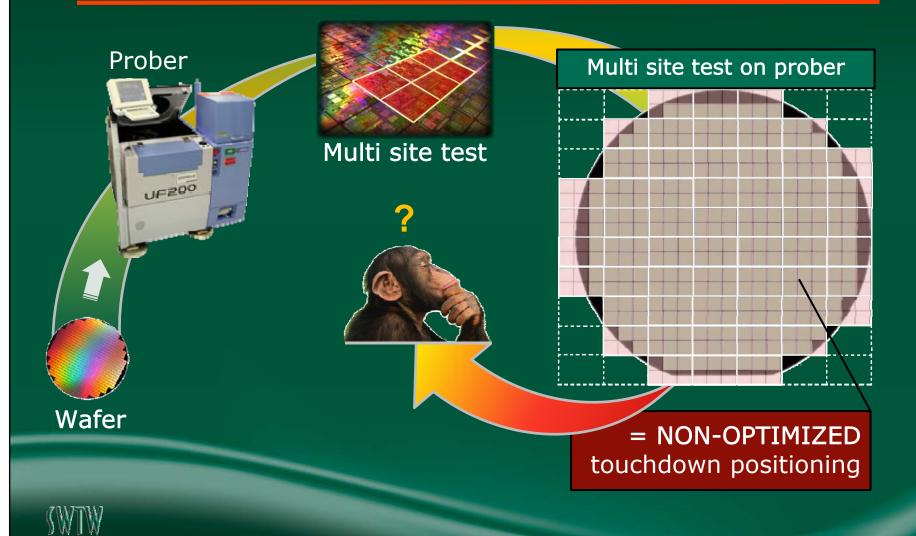
Multi site test



= NON-OPTIMIZED touchdown positioning

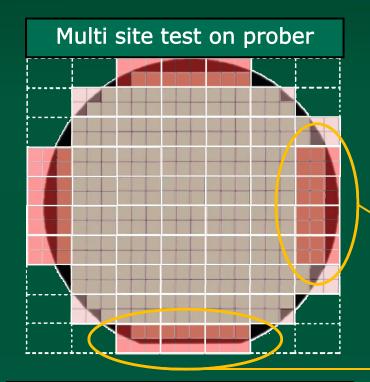


Wafer



MULTI SITE TEST SITUATION

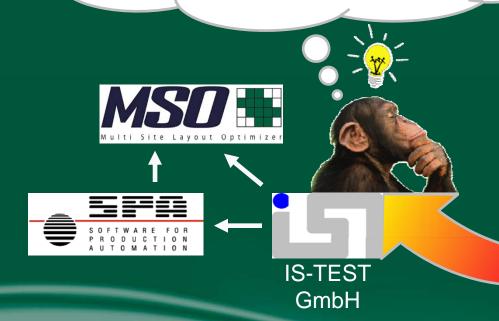
- Most probers do <u>not</u> supply any intelligent stepping algorithms
- Unnecessary high amount of touchdowns to process
- As a result: long process times



Highlighted fields signalize potential touchdown surplus!



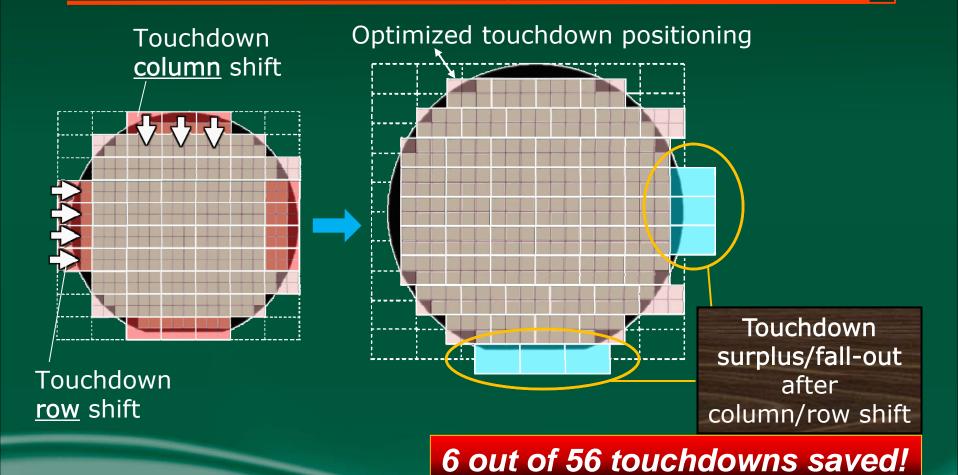
Create a program that minimizes touchdowns by <u>automatic</u> shifting of touchdown coordinates.



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PRIMARY GOAL: minimize total amount of touchdowns





MSO

Basics and facts

The benefits and usability of MSO



INTRODUCTION

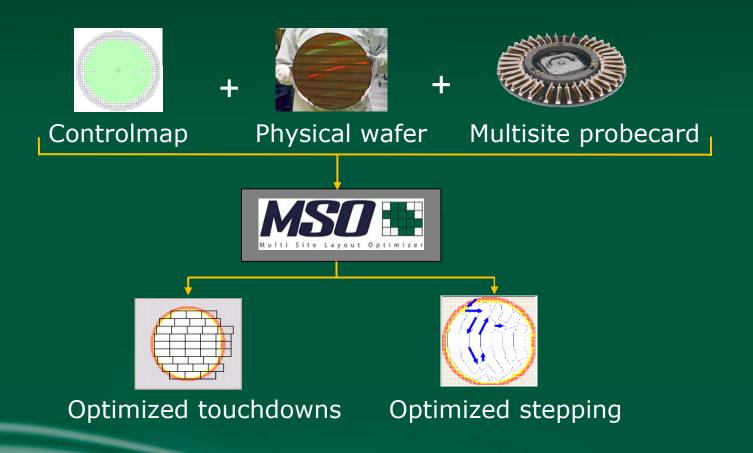
The Multi Site Layout Optimizer (MSO) is an easy to use software for optimizing multisite layouts.

The benefits:

- Less touchdowns
 - Optimized probing path
 - Optimized hot probing
 - Find ideal probecard layout

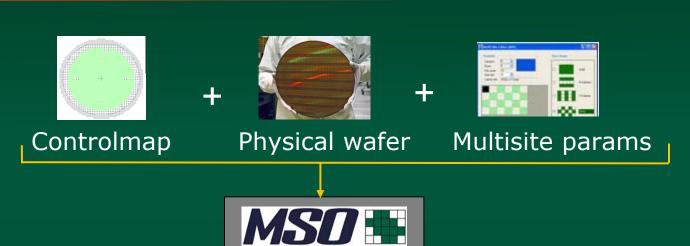


MSO workflow A





MSO workflow B





Ideal multi site probecard layout



MSO

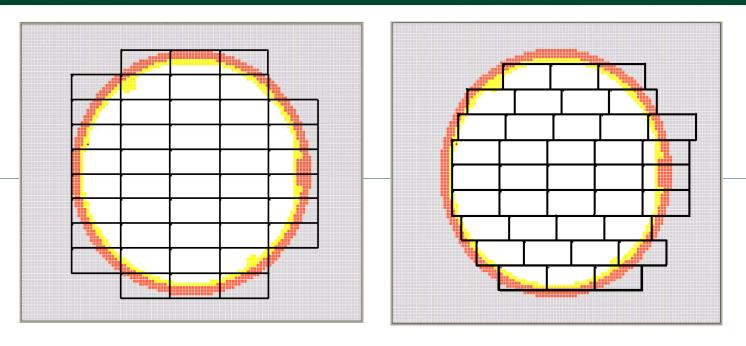
Example

Complete Optimization

Touchdowns and stepping path



MINIMIZE TOUCHDOWNS



Prober: 44 Tochdowns

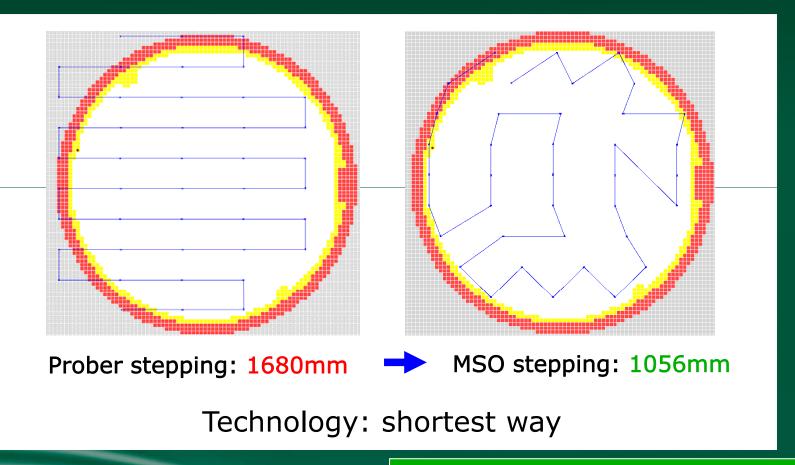
MSO: 38 Touchdowns

Technology: automatic column / row shift

= 14,6 % TD reduction!



OPTIMIZE PROBING PATH



= ~37 % Stepping reduction!



TEST-COST REDUCTION

Wafertype/Prober parameters

Dies to test / Wafer = 3.823 Test Time / TD = 5 sec.

Number of DUT = 128 X/Y Stepping / sec = 100mm

	Non-optimized	MSO
Number of TD / Wafer	44 TD	38 TD
Test time / Wafer	220 sec.	190 sec.
X/Y Stepping / Wafer	1680 mm	1056 mm
Stepping Time / Wafer	17 sec.	11 sec.

<u>Process time</u> reduction /wafer = 36 sec.

Total Test Time / Wafer

= ~<u>15%</u>

201 sec.



TEST COST REDUCTION!

237 sec.

MSO

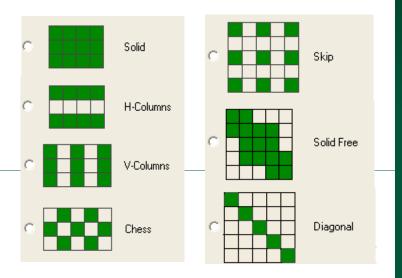
Feature Overview

Multi site layouts and touchdown options

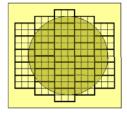


MSO TOUCHDOWN OPTIONS

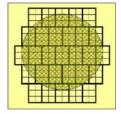
Multi site shape options:



Touchdown shifting algorithms:



COL shift

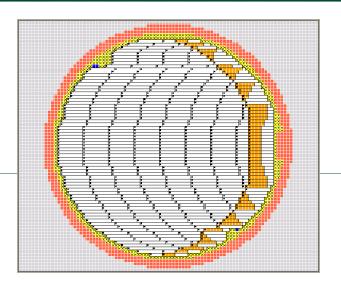


ROW shift

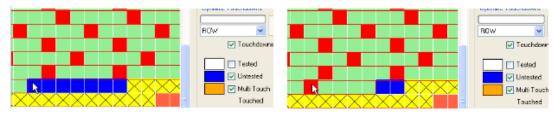


MSO TOUCHDOWN OPTIONS

Untouchable die zones (=> overlappings/untested)



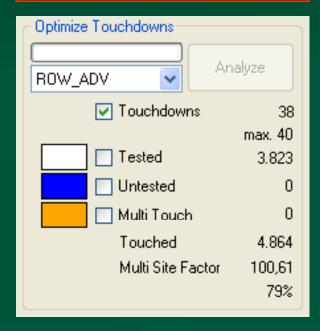
Manual touchdown edit



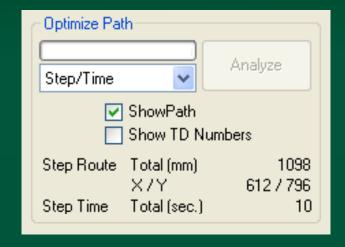


MSO RESULT DATA

Touchdown data



Stepping path data



MSO

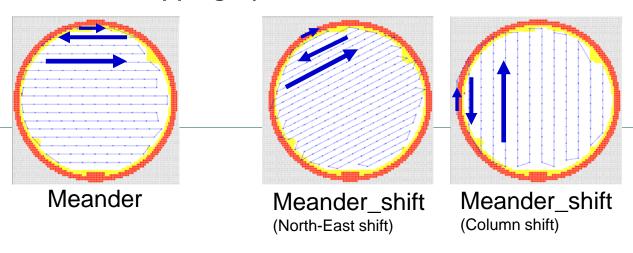
Feature Overview

Stepping path algorithms

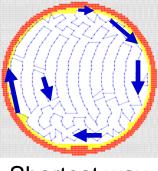


MSO STEPPING OPTIONS

Meander stepping options



Time optimized stepping

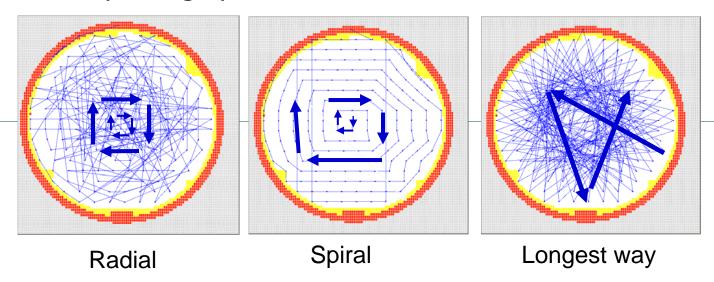


Shortest way



MSO STEPPING OPTIONS

Hot probing optimizations *



Optimized stepping for more uniform heat expansion of probe card, tester interface and prober head plate.

* BLEYL, et al, SWTW 2011



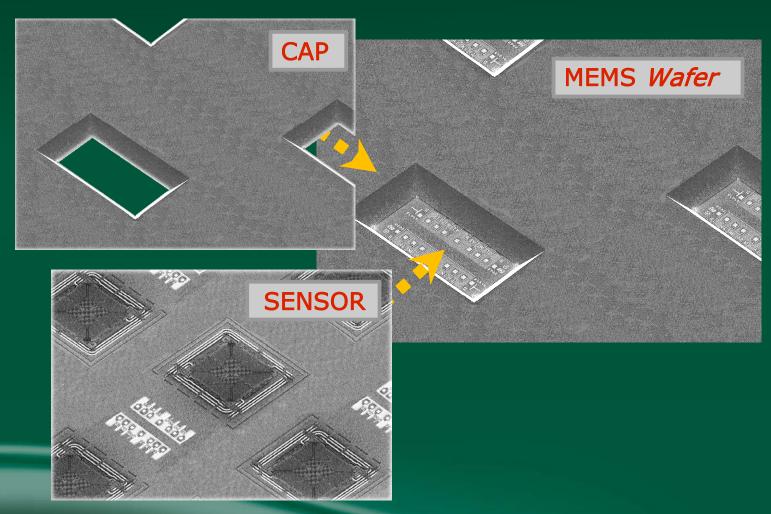


MEMS wafer test

:: a multi site quest ::



MEMS Waferprocess

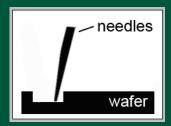


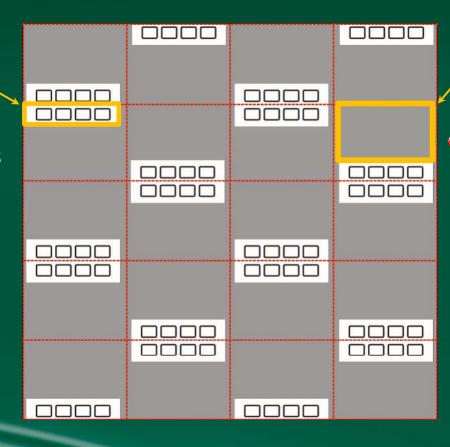


MEMS chip structure

SENSOR test pads •

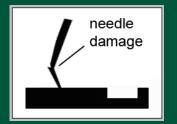
- electrical testing
- probecard needles contact area





CAP wafer surface

NO-contact area for probecard needles

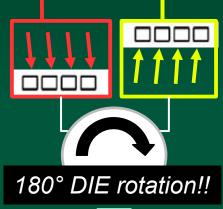




MEMS test pads

Probecard needles

position #1
on MEMS die



Probecard needles position #2

on MEMS die



Alternating needle position on dies!



MEMS wafer test

Single Site probing



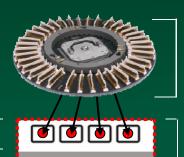




MEMS single site test

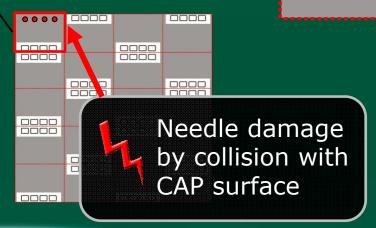


Needles contacting <a href="https://www.upper.com/upper.

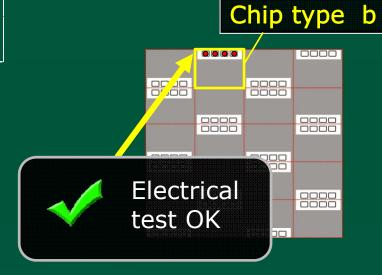


Probecard layout

Chip type a



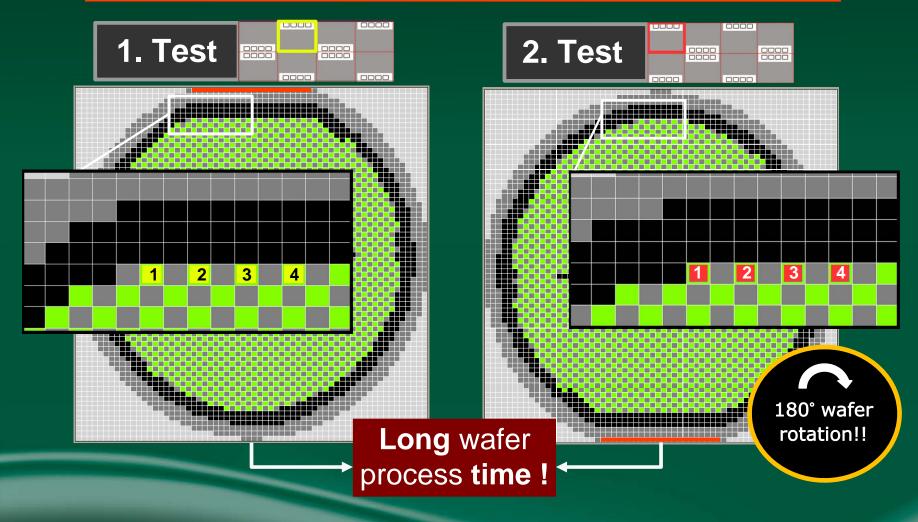
MEMS die







MEMS single site test





MEMS Wafertest

Why not process
MEMS wafer within
ONE
test cycle?



MEMS Wafertest

Multi Site Probing !!!



What are the potential blocking points

for multi site testing

MEMS devices?

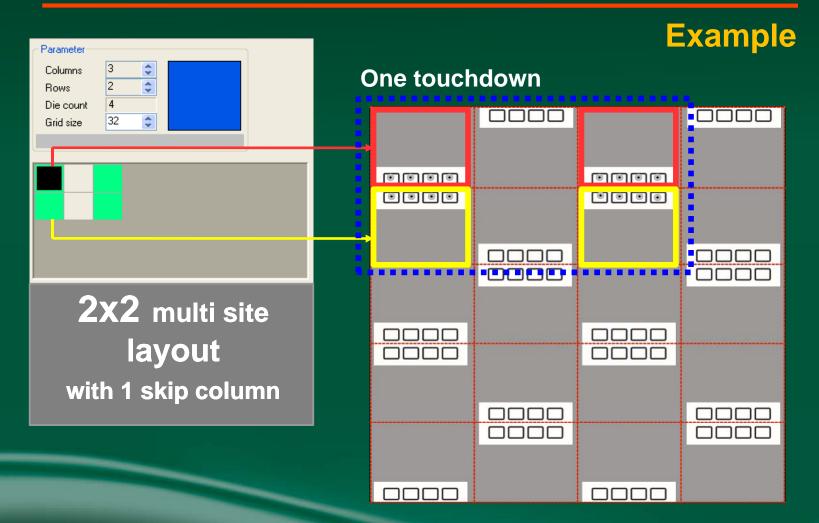


Blocking points?

Probecard site needles touching the CAP Wafer surface (causing damage)

- → Needles touching <u>CAP</u> area of die
- → Needles touching wafer <u>EDGE</u> area

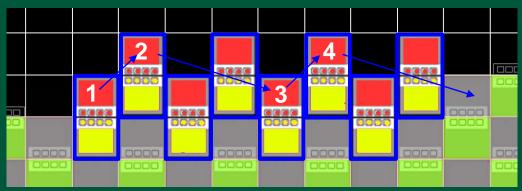








First touchdown

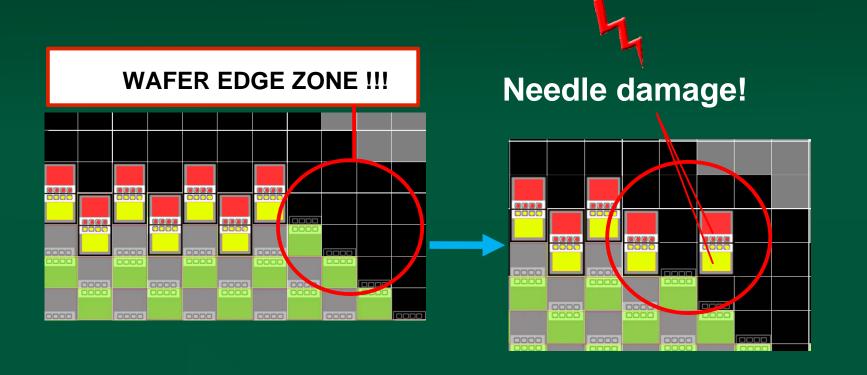


Special stepping algorithm for MEMS to avoid CAP contact



MEMS device can be tested in **ONE** probing cycle!



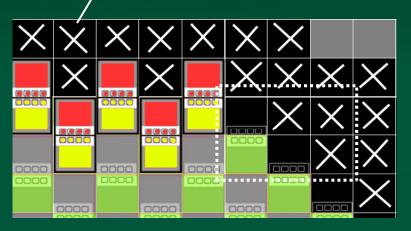


SOLUTION → see next page

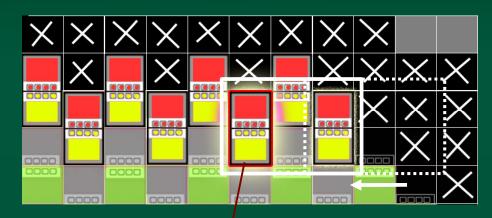


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UNTOUCHABLE DIES



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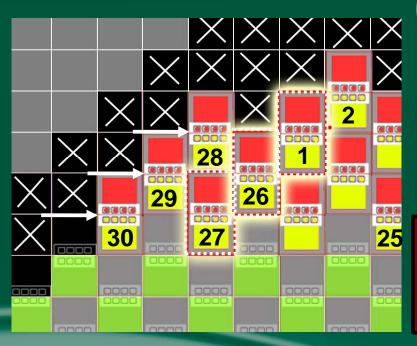
<u>Automatic</u> touchdown repositioning

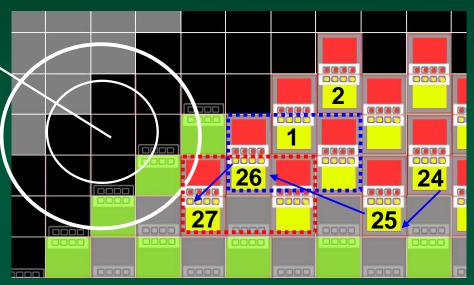
→ creating 2 double touched dies!

=> Safe needle contacting via untouchable die zones!



WAFER EDGE ZONE!!!





Automatic touchdown repositioning → creating 6 double touched dies here!



Blocking points?

Contact of probecard and

CAP/EDGE wafer can

be avoided by intelligent

touchdown positioning!



SUMMARY

- MSO optimized touchdown positioning increases prober test efficiency and saves process time!
- MSO is able to provide special stepping path algorithms, which are useful to:
 - compensate probing-related problems such as needle expansions during HOT PROBING (already used by customer NXP)
 - handle wafer-specific features and optimize the test process (e.g. MEMS / future prospect)



ACKNOWLEDGEMENTS

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THANK YOU VERY MUCH FOR YOUR ATTENTION!

Questions?



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